

NEGATIVE TYPE FLUORINE-CONTAINING RESIST COMPOSITION

Patent number: JP2002090996
Publication date: 2002-03-27
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Classification:
- international: G03F7/038; C08F214/18; C08K5/00; C08K5/16; C08L27/12; C08L29/10; G03F7/004; H01L21/027
- european:
Application number: JP20000281167 20000918
Priority number(s):

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Abstract of JP2002090996

PROBLEM TO BE SOLVED: To provide a negative type resist composition excellent in transparency particularly to radiation and dry etching resistance as a chemical amplification type resist and giving a resist pattern excellent in sensitivity, resolution, flatness, heat resistance, etc.

SOLUTION: The negative type fluorine-containing resist composition contains a fluoropolymer (X) having a monomer unit containing an acidic hydroxyl group as a constitutional unit, an acid generating compound (Y) which generates an acid when irradiated with light, an aminoplast (Z) and an organic solvent (D).

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